

**INDUSTRY STANDARD OF THE
PEOPLE'S REPUBLIC OF CHINA**

SJ 20842-2002

Test method for Ga/As ratio of surface of gallium arsenide

砷化镓表面砷镓比的测试方法

(English Translation)

Issued on: October 30, 2002

Implemented on: March 1, 2003

Issued by: Ministry of Industry and Information Technology of PRC

Table of Contents

What this standard covers	1
Document data	2

What this standard covers

This standard specifies the ratio of gallium arsenide GaAs surface X-ray photoelectron spectroscopy test methods. This standard applies to GaAs devices for monitoring various surface treatment during the manufacturing process of the gallium arsenide GaAs wafer surface than the impact, but also suitable for wafer processing in a variety of surface treatment.

Document data

Chinese classification (CCS): H83;L90.

Estimated length of the Chinese original: 5,528 words.